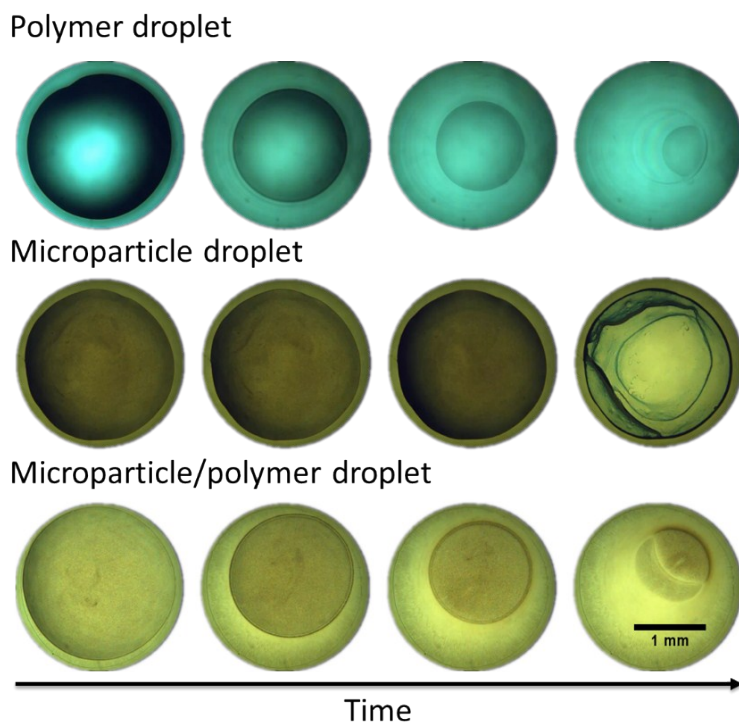


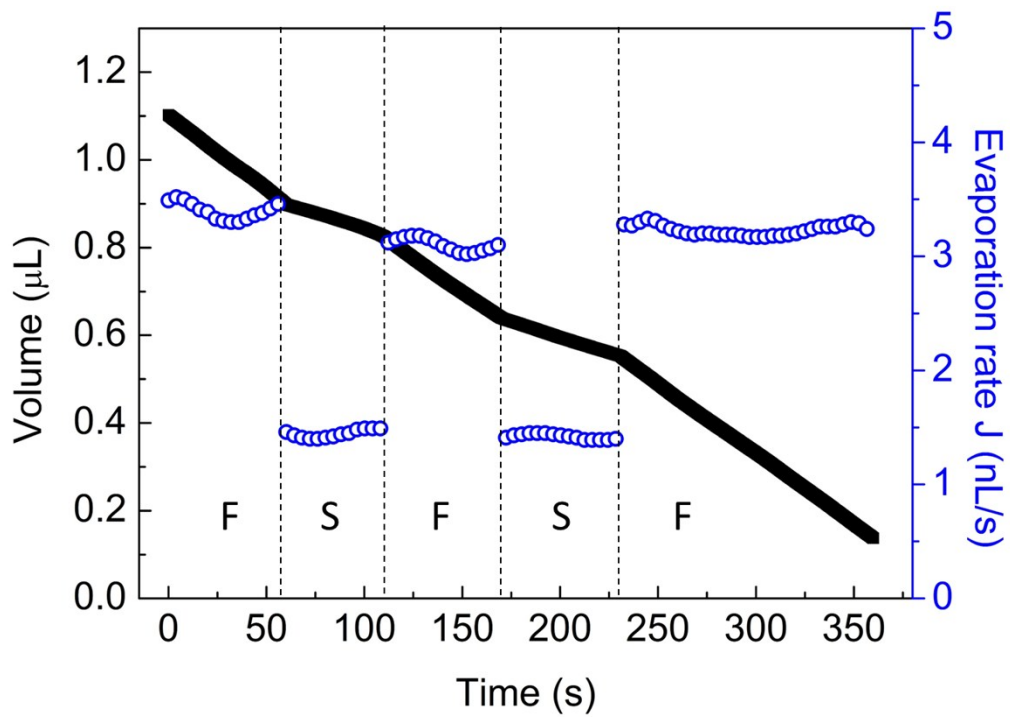
## SUPPORTING INFORMATION

### Evaporation Controlled Particle Patterns in a Polymer Droplet

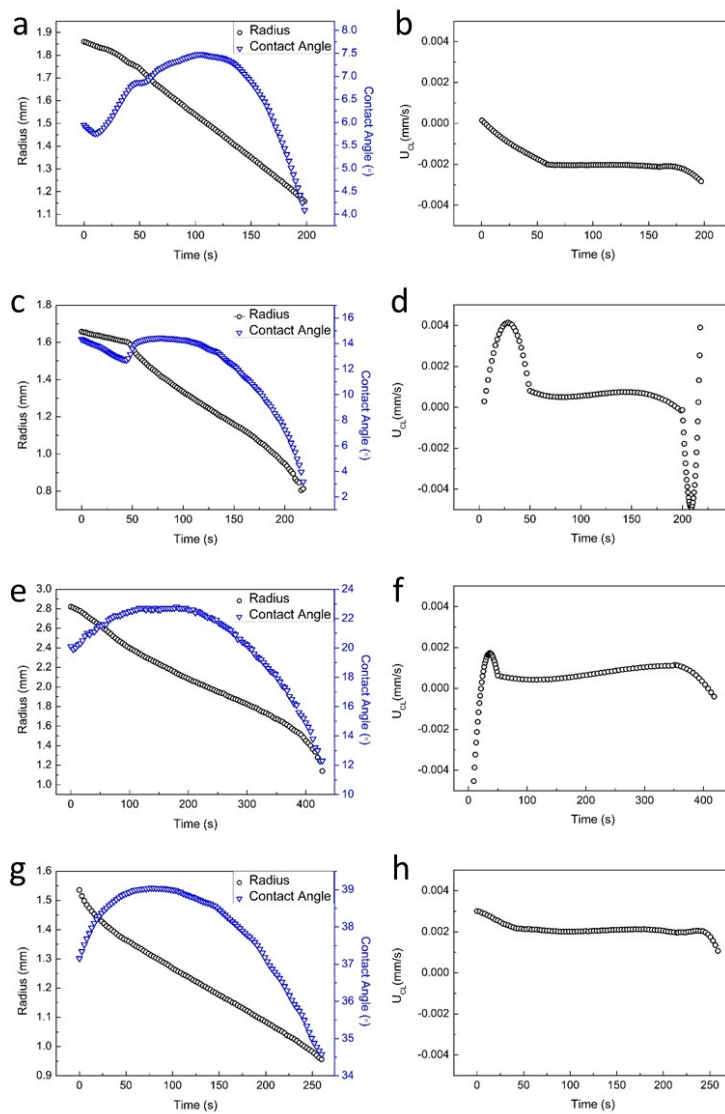
Chongfeng Zhang and Pinar Akcora\*



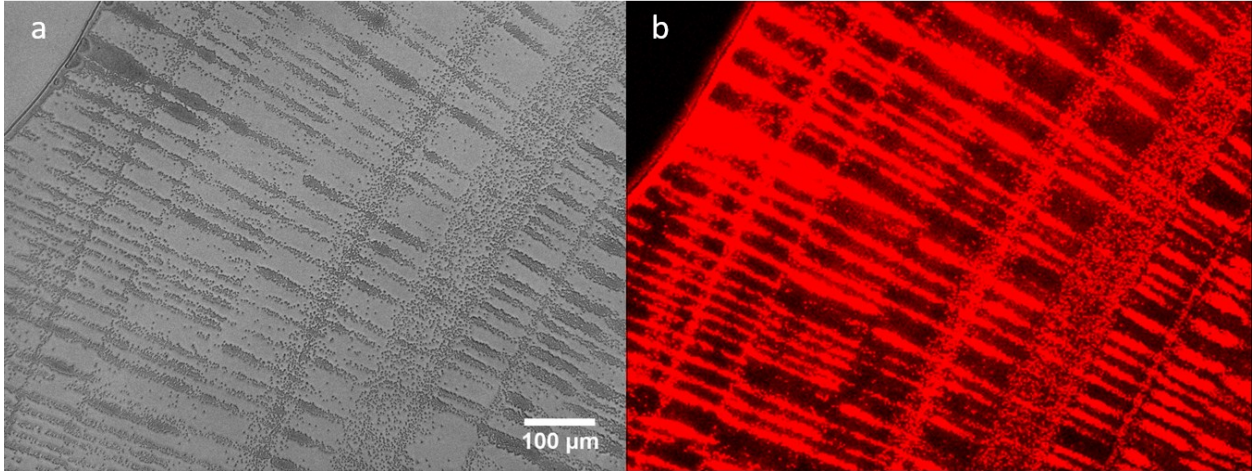
**Figure S1.** Top-view optical microscope images of water droplets containing pure PVP (top), PS particles (middle), and PS microparticles in PVP (bottom) on piranha-treated glass substrates during drying. A typical pinning of contact line is observed in evaporating colloidal particle drop, whereas the contact lines of pure polymer and microparticle/polymer droplets recede freely.



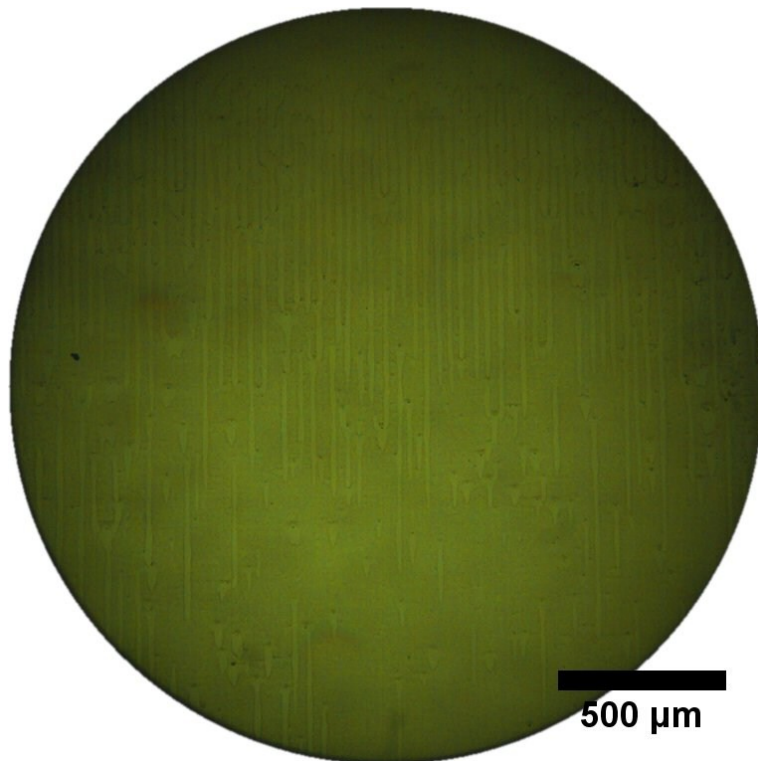
**Figure S2.** Droplet volume and evaporation rate changes with time.



**Figure S3.** Evolution of radius and contact angle for microparticle/polymer droplet under ambient environment on (a) mica, (c) piranha-glass, (e) piranha-silicon and (g) acetone-glass; the corresponding  $U_{CL}$  change on (b) mica, (d) piranha-glass, (f) piranha-silicon and (i) acetone-glass



**Figure S4.** Optical (a) and confocal (b) images of polymer solution with 1  $\mu\text{m}$  and 100 nm fluorescently labeled PS particles (0.2mg/ml). Some nanoparticles are deposited between stripes.



**Figure S5.** optical images of continuously withdrawn substrate from nanoparticle/polymer solution. Parallel stripes are formed on top of dipped substrates

**Determining contact angle in tensiometer:**

The net force on substrate using tensiometer is calculated by  $F = P\gamma_{lv}\cos\theta - \rho_l g A x$ .  $P$  is the length of contact line and equals  $P = 2(t + w)$ ,  $t$  is the thickness and  $w$  is the width of substrate,  $A$  is the cross-section area of substrate ( $A = tw$ ),  $x$  is the immersion depth.  $P\gamma_{lv}\cos\theta$  is interfacial force and  $\rho_l g A x$  is buoyant force.